

A cross-sectional view of a semiconductor device 100. The device features a substrate 108 with a well 108 formed in it. A layer 102 is disposed on the substrate 108. A layer 104 is disposed on top of layer 102. A layer 106 is disposed on top of layer 104. A layer 110 is disposed on top of layer 106. A layer 112 is disposed on top of layer 110. A layer 114 is disposed on top of layer 112. A layer 116 is disposed on top of layer 114. A layer 102 is also disposed on top of layer 106. A layer 104 is also disposed on top of layer 106. A layer 106 is also disposed on top of layer 106. A layer 110 is also disposed on top of layer 106. A layer 112 is also disposed on top of layer 106. A layer 114 is also disposed on top of layer 106. A layer 116 is also disposed on top of layer 106.

FIG. 1
(PRIOR ART)

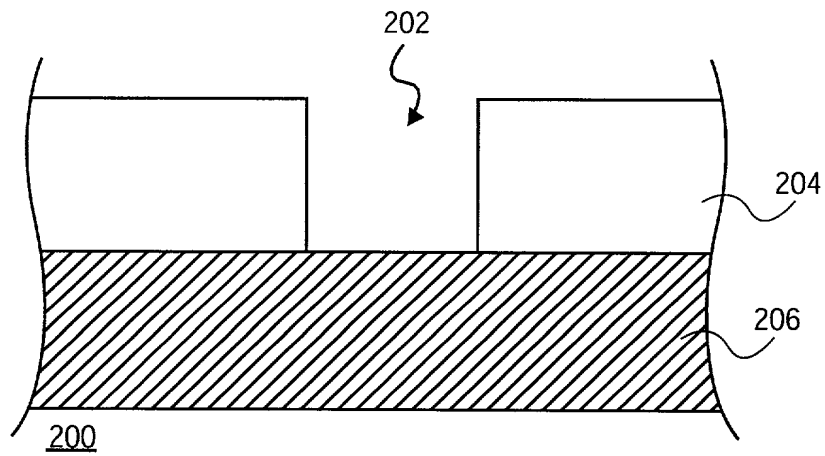


FIG. 2
(PRIOR ART)

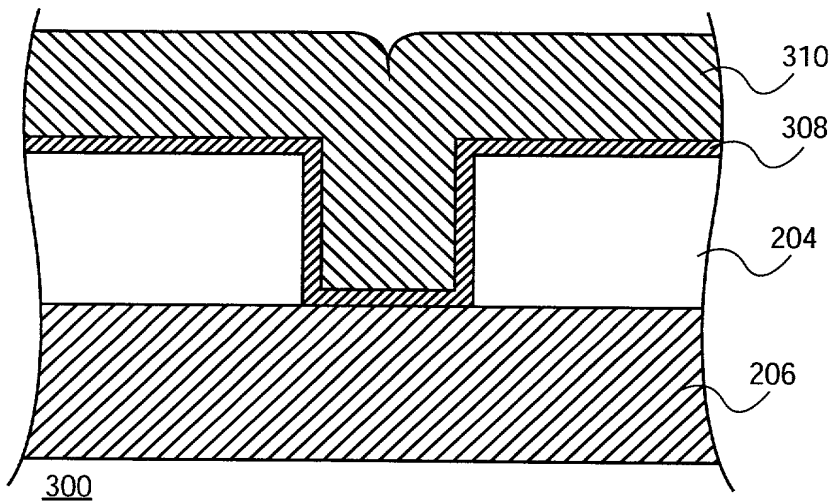


FIG. 3
(PRIOR ART)

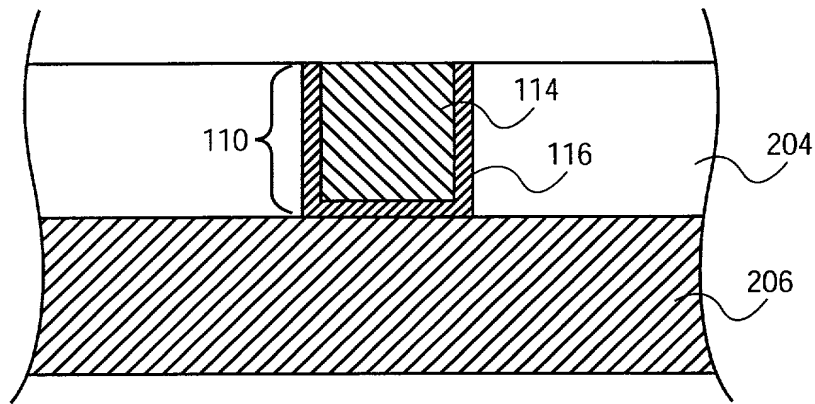


FIG. 4
(PRIOR ART)

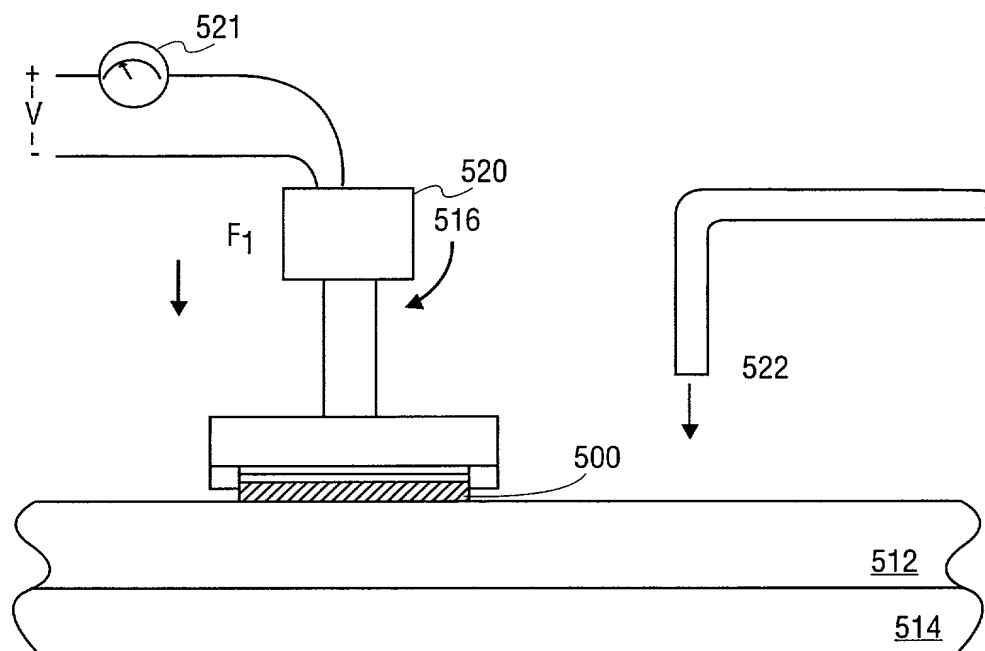


FIG. 5

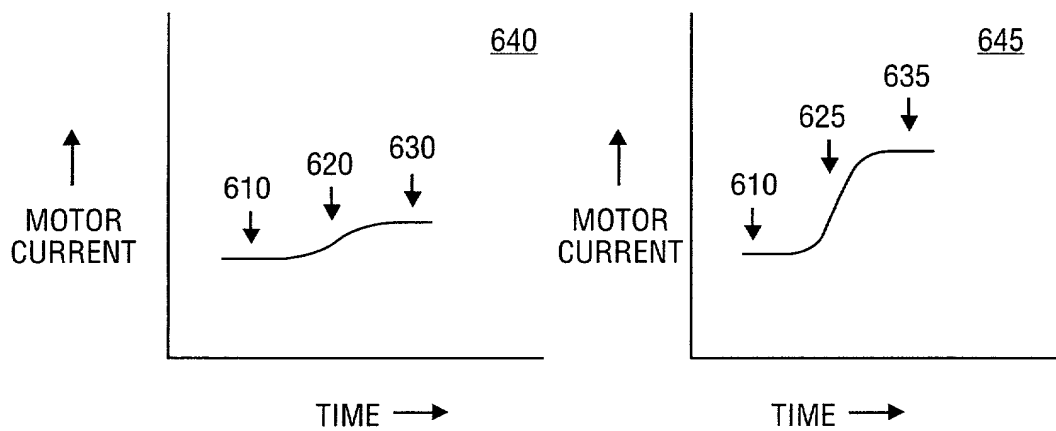


FIG. 6

REMOVING EXCESS VIA MATERIAL FROM
AN INTEGRATED CIRCUIT WAFER
BY CHEMICAL MECHANICAL POLISHING
THE WAFER WITH A SLURRY AND AN
OXIDATION AGENT FOR THE VIA
MATERIAL ON A SURFACE
710



MONITORING THE CURRENT REQUIRED TO
ROTATE THE WAFER ON THE SURFACE AS
A MEASURE OF THE EXCESS VIA
MATERIAL REMOVAL ENDPOINT
720



OPTIMIZING THE ENDPOINT SIGNAL BY
BUFFERING A SLURRY USED IN THE
CHEMICAL MECHANICAL POLISH
730

FIG. 7